

NCCAUS
Junction Technologies User Group Meeting
“Updates on New Technologies”
Friday, July 12, 2019

Sponsors:

Sumitomo Heavy Industries Ion Technology

Axcelis

UC Components

Co-Chairs:

Susan Felch

John Borland

Michael Current

Agenda

1:00-1:15 p.m. Sue Felch, Susan Felch Consulting
Introduction and IIT2020 Announcement

1:15-1:45 p.m. "Novel Approach to Remove Films at Room Temperature Isotropically & Atomically with Rapid Thermal Pulse Sequences", Y.S. Kim, Lam Research

1:45-2:30 p.m. "Review of Applications of Defect Photoluminescence Imaging (DPLI) during IC Processing", John Byrnes, Semilab

2:30-2:45 p.m. Break/Refreshments

2:45-3:30 p.m. "Aspects of Highly-Channeled MeV Dopant Implants in Si(100): Profiles & Defects", Michael Current, Current Scientific

3:30-4:00 p.m. "Comprehensive Characterization of B+ Implanted Si after Rapid Thermal Annealing", Woo Sik Yoo, WaferMasters

4:00-4:30 p.m. "Expand Laser Annealing for Low Thermal Budget Applications", Shaoyin Chen, Ultratech/Veeco

4:30 p.m. Closing remarks

IIT 2020



- Conference: Sunday - Thursday, Sept. 20-24, 2020
- School: Thursday - Saturday, Sept. 17-19, 2020
- Location: US Grant Hotel, 326 Broadway, San Diego, CA
- Co-Chairs: Mitch Taylor, Susan Felch, Aaron Vanderpool, Wilfried Lerch, Larry Larson
- General topics: implant/doping and annealing technologies, processes, device applications, equipment, metrology, and modeling
- Abstracts due: May 2020
- Administrative support: Materials Research Society (MRS)
- Everyone must opt in via MRS website to receive conference information and Call for Papers (EU GDPR)
 - Create MRS account at www.mrs.org/alerts
 - Conference website: www.mrs.org/iit2020
- For additional information, contact Susan Felch at sfelch@sbcglobal.net

